<u>Abstract</u>

The present invention relates to a photoresist composition comprising a photoacid generator and at least one polymer comprising at least one unit as described by structure 1,

$$\begin{array}{c}
R_{1} \\
(X)_{m} \\
R_{f} - C - R_{2} \\
\downarrow \\
O \\
(R_{3} - C - R_{4})_{p} \\
C - O \\
\downarrow \\
C + O \\
\downarrow \\
C + O
\end{array}$$
(1)

The invention also relates to a process for imaging the photoresist composition of the present invention, and to a process of making the polymer in the presence of an organic base.

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